	Hits	Search Text	DBs
22		(ion near9 beam near9 deposit\$4)) near16 (mask or pattern) near16 (conformal\$4 or sidewall or side	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
23	28	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) near16 (sputter\$4 or PVD or (physical near4 vapor) or deposit\$4 or coat\$4 or (ion near9 beam near9 deposit\$4)) near16 (mask or pattern) near16 (conformal\$4 or sidewall or side	USPAT; FPRS; EPO; JPO;
25	0	((silicon or "Si" or polysilicon or (polycrystalline near4 silicon)) near16 (sputter\$4 or PVD or (physical near4 vapor) or deposit\$4 or coat\$4 or (ion near9 beam near9 deposit\$4)) near39 (photoresist or resist) near16 (mask or pattern or feature) near16 (conformal\$4 or sidewall	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
26	14	(pattern or mask or feature) same (conformal\$4 or sidewall or side	USPAT; FPRS; EPO; JPO;